

L Number	Hits	Search Text	DB	Time stamp
1	16	jp-2000159758-\$.did. jp-2002131917-\$.did. jp-11305444-\$.did. jp-2001142213-\$.did. jp-2001188346-\$.did. jp-2001240625-\$.did. jp-2002116546-\$.did. jp-2002296783-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 13:56
2	38	(US-6448420-\$ or US-6280898-\$ or US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$.did. or (US-20020009666-\$ or US-20010041303-\$ or US-20020132181-\$ or US-20020098441-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$.did. or (JP-2001142213-\$ or JP-2001188346-\$ or JP-2001240625-\$.did.	USPAT; US-PGPUB; JPO	2003/10/24 14:19
3	41	(((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))) and (lactone)) and (((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or US-6280898-\$.did. or (US-20010041303-\$ or US-20020009666-\$ or US-20020132181-\$ or US-20020098441-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$.did.) ((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOA I AOA I-T AOAI-TOSHIAKI AOA I-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:20

East Don't Remove

4	18	<p>(((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))) and (lactone)) and (((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or US-6280898-\$).did. or (US-20010041303-\$ or US-20020009666-\$ or US-20020132181-\$ or US-20020098441-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$).did.) ((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOA I AOA I-T AOA I-TOSHI AKI AOA I-TOSHI AKI-C-O-FUGI-PHOTO-F AOA I-TOSHI AKI-C-O-FUJI-PHOTO-F)))) not ((US-6448420-\$ or US-6280898-\$ or US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$).did. or (US-20020009666-\$ or US-20010041303-\$ or US-20020132181-\$ or US-20020098441-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$).did. or (JP-2001142213-\$ or JP-2001188346-\$ or JP-2001240625-\$).did.)</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:20
5	341	(resist photoresist) and (lactone) and ((maleic adj anhydride) (maleimide)) and (norbornene norbornyl)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:41
6	17155	(acid photoacid) near generat\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:41
7	87099	positive near5 (composition working image pattern type)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:44
8	4069	((acid photoacid) near generat\$4) and (positive near5 (composition working image pattern type))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:45

9	235	((((acid photoacid) near generat\$4) and (positive near5 (composition working image pattern type))) and ((resist photoresist) and (lactone) and ((maleic adj anhydride) (maleimide)) and (norbornene norbornyl)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:45
10	202	(((acid photoacid) near generat\$4) and (positive near5 (composition working image pattern type))) and ((resist photoresist) and (lactone) and ((maleic adj anhydride) (maleimide)) and (norbornene norbornyl))) not ((jp-2000159758-\$.did. jp-2002131917-\$.did. jp-11305444-\$.did. jp-2001142213-\$.did. jp-2001188346-\$.did. jp-2001240625-\$.did. jp-2002116546-\$.did. jp-2002296783-\$.did.) ((US-6448420-\$. or US-6280898-\$. or US-6403280-\$. or US-6388101-\$. or US-6329125-\$. or US-6303266-\$. or US-6284429-\$. or US-6270941-\$. or US-6251560-\$. or US-6248920-\$. or US-6207342-\$. or US-6200725-\$. or US-6077644-\$. or US-6013416-\$. or US-5968713-\$. or US-5929271-\$. or US-5910392-\$.).did. or (US-20020009666-\$. or US-20010041303-\$. or US-20020132181-\$. or US-20020098441-\$. or US-20020081523-\$. or US-20020061465-\$. or US-20020058201-\$. or US-20020051936-\$. or US-20020051935-\$. or US-20020048724-\$. or US-20020009668-\$. or US-20020009667-\$. or US-20020004569-\$. or US-20010038969-\$. or US-20010033989-\$. or US-20010018162-\$. or US-20010010890-\$. or US-20010003640-\$.).did. or (JP-2001142213-\$. or JP-2001188346-\$. or JP-2001240625-\$.).did.) (((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))) and (lactone)) and (((US-6403280-\$. or US-6388101-\$. or US-6329125-\$. or US-6303266-\$. or US-6284429-\$. or US-6270941-\$. or US-6251560-\$. or US-6248920-\$. or US-6207342-\$. or US-6200725-\$. or US-6077644-\$. or US-6013416-\$. or US-5968713-\$. or US-5929271-\$. or US-5910392-\$. or US-6448420-\$. or US-6280898-\$.).did. or (US-20010041303-\$. or US-20020009666-\$. or US-20020132181-\$. or US-20020098441-\$. or US-20020081523-\$. or US-20020061465-\$. or US-20020058201-\$. or US-20020051936-\$. or US-20020051935-\$. or US-20020048724-\$. or US-20020009668-\$. or US-20020009667-\$. or US-20020004569-\$. or US-20010038969-\$. or US-20010033989-\$. or US-20010018162-\$. or US-20010010890-\$. or US-20010003640-\$.).did.) (((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOA I AOA I-T AOA I-TOSHIAKI AOA I-TOSHIAKI-C-O-FUGI-PHOTO-F AOA I-TOSHIAKI-C-O-FUJI-PHOTO-F))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:45
11	70187	nitrogen and surfactant	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:47

12	113	(nitrogen and surfactant) and ((((((acid photoacid) near generat\$4) and (positive near5 (composition working image pattern type)))) and ((resist photoresist) and (lactone) and ((maleic adj anhydride) (maleimide)) and (norbornene norbornyl))) not ((jp-2000159758-\$.did. jp-2002131917-\$.did. jp-11305444-\$.did. jp-2001142213-\$.did. jp-2001188346-\$.did. jp-2001240625-\$.did. jp-2002116546-\$.did. jp-2002296783-\$.did.) ((US-6448420-\$. or US-6280898-\$. or US-6403280-\$. or US-6388101-\$. or US-6329125-\$. or US-6303266-\$. or US-6284429-\$. or US-6270941-\$. or US-6251560-\$. or US-6248920-\$. or US-6207342-\$. or US-6200725-\$. or US-6077644-\$. or US-6013416-\$. or US-5968713-\$. or US-5929271-\$. or US-5910392-\$.).did. or (US-20020009666-\$. or US-20010041303-\$. or US-20020132181-\$. or US-20020098441-\$. or US-20020081523-\$. or US-20020061465-\$. or US-20020058201-\$. or US-20020051936-\$. or US-20020051935-\$. or US-20020048724-\$. or US-20020009668-\$. or US-20020009667-\$. or US-20020004569-\$. or US-20010038969-\$. or US-20010033989-\$. or US-20010018162-\$. or US-20010010890-\$. or US-20010003640-\$.).did. or (JP-2001142213-\$. or JP-2001188346-\$. or JP-2001240625-\$.).did.) (((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))) and (lactone)) and (((US-6403280-\$. or US-6388101-\$. or US-6329125-\$. or US-6303266-\$. or US-6284429-\$. or US-6270941-\$. or US-6251560-\$. or US-6248920-\$. or US-6207342-\$. or US-6200725-\$. or US-6077644-\$. or US-6013416-\$. or US-5968713-\$. or US-5929271-\$. or US-5910392-\$. or US-6448420-\$. or US-6280898-\$.).did. or (US-20010041303-\$. or US-20020009666-\$. or US-20020132181-\$. or US-20020098441-\$. or US-20020081523-\$. or US-20020061465-\$. or US-20020058201-\$. or US-20020051936-\$. or US-20020051935-\$. or US-20020048724-\$. or US-20020009668-\$. or US-20020009667-\$. or US-20020004569-\$. or US-20010038969-\$. or US-20010033989-\$. or US-20010018162-\$. or US-20010010890-\$. or US-20010003640-\$.).did.) (((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOA I AOA I-T AOA I-TOSHIAKI AOA I-TOSHIAKI-C-O-FUGI-PHOTO-F AOA I-TOSHIAKI-C-O-FUJI-PHOTO-F))))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 16:20
13	2	("6579659").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 16:55
14	0	6579659.URPN.	USPAT	2003/10/24 16:20
15	6	("5968713" "6013416" "6068512" "6200725" "6280898" "6492091" "2001/0003640").PN.	USPAT	2003/10/24 16:21
16	6706	(fluorine silicon) near5 surfactant	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:09

17	4693585	conventional improvement enhance enhancement improve benefit beneficial	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 16:57
18	930	((fluorine silicon) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 16:59
19	0	((fluorine silicon) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial)) and (positive near5 (composition working image pattern type)) and ((acid photoacid) near generat\$4) and ((resist photoresist) and (lactone) and ((maleic adj anhydride) (maleimide)) and (norbornene norbornyl))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:00
20	49	((fluorine silicon) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial)) and (positive near5 (composition working image pattern type)) and ((acid photoacid) near generat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:10
21	24	((fluorine silicon) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial)) and (positive near5 (composition working image pattern type)) and ((acid photoacid) near generat\$4)	USPAT	2003/10/24 17:06
22	2	("4822713").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:06
23	138	(fluorine-type silicon-type) near5 surfactant	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:10
24	4	((fluorine-type silicon-type) near5 surfactant) and (positive near5 (composition working image pattern type)) and ((acid photoacid) near generat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:11
26	13952	((fluorine-type silicon-type) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial)) amd (positive near5 (composition working image pattern type)) and ((acid photoacid) near generat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:11
27	0	((fluorine-type silicon-type) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial)) and (positive near5 (composition working image pattern type)) and ((acid photoacid) near generat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:12
28	1	((fluorine-type silicon-type) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial)) and (positive near5 (composition working image pattern type))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:12
25	18	((fluorine-type silicon-type) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:12
-	1863077	resin resist photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 13:55
-	8221	(resin resist photoresist) and (acid near generat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 12:17

-	1522	"3" and (positive near composition)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 12:24
-	203	((resin resist photoresist) and (acid near generat\$4)) and (positive near composition)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 12:24
-	3892	((resin resist photoresist) and (acid near generat\$4)) and (positive)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 12:43
-	0	("us-20010039080-A1.did.").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 12:32
-	2	("20010039080").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 12:32
-	0	20010039080.URPN.	USPAT	2002/10/10 12:43
-	801	((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 14:19
-	288	((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:45
-	721	SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/15 14:57
-	30	(((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/04/29 09:41
-	258	(((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) not ((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 16:06
-	79	(((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) not ((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))) and (lactone)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/15 14:57
-	289	(((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/15 15:00

-	723	SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/15 15:01
-	259	((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) not (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/15 15:01
-	79	((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) not ((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))) and (lactone)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/15 15:01
-	180	(((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) not (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)) not (((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) not ((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))) and (lactone))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/15 16:11
-	2	US-20010039080-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/15 19:07
-	549	(resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/16 11:41
-	96	((resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)) and((norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/16 11:44
-	71	(((resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)) and((norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3))) and positive	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:20
-	325	norbornene same (acrylate methacrylate) same (maleic adj anhydride)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/16 11:54
-	7	"6284429"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/16 14:53
-	2	("6284429").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/16 14:53

35	(US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or US-6280898-\$).did. or (US-20010041303-\$ or US-20020009666-\$ or US-20020132181-\$ or US-20020098441-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$).did.	USPAT; US-PGPUB	2003/04/29 09:39
343	(((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/04/29 09:43
44	(((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOA I AOA I-T AOA I-TOSHIAKI AOA I-TOSHIAKI-C-O-FUGI-PHOTO-F AOA I-TOSHIAKI-C-O-FUJI-PHOTO-F)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:39
118	((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))) and (lactone)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/04/29 09:44
77	((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or US-6280898-\$).did. or (US-20010041303-\$ or US-20020009666-\$ or US-20020132181-\$ or US-20020098441-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$).did.) (((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOA I AOA I-T AOA I-TOSHIAKI AOA I-TOSHIAKI-C-O-FUGI-PHOTO-F AOA I-TOSHIAKI-C-O-FUJI-PHOTO-F))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/04/29 09:44

38	<p>((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))) and (lactone)) and (((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or US-6280898-\$).did. or (US-20010041303-\$ or US-20020009666-\$ or US-20020132181-\$ or US-20020098441-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$).did.) (((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)))</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:19
157	<p>((((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))) and (lactone)) (((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or US-6280898-\$).did. or (US-20010041303-\$ or US-20020009666-\$ or US-20020132181-\$ or US-20020098441-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$).did.) (((((resin resist photoresist) and (acid near generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)))</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/04/29 09:44